

IN THE CLAIMS:

Please CANCEL claims 1-25 and 32 without prejudice to or disclaimer of the recited subject matter.

Please ADD new claims 33-45, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-32. (Cancelled)

33. (New) An electrooptic system for charged-particle beams, the system comprising:

a first layer having a plurality of first apertures through which the charged-particle beams pass;

a second layer having a plurality of second apertures through which the charged-particle beams pass and a plurality of electrodes; and

a conductive shield layer interposed between the first layer and the second layer.

34. (New) The system according to claim 33, wherein the conductive shield layer has a plurality of third apertures through which the charged-particle beams pass.

35. (New) The system according to claim 34, wherein a size of the third aperture is larger than that of the first aperture or the second aperture.

36. (New) The system according to claim 33, wherein the conductive shield layer is arranged to be substantially parallel to the first layer and the second layer.

37. (New) The system according to claim 33, wherein a thickness of the conductive shield layer is thicker than that of the first layer or the second layer.

38. (New) The system according to claim 33, further comprising an insulating layer interposed between the first layer and the conductive shield layer.

39. (New) The apparatus according to claim 33, wherein the second layer is insulated from the conductive shield layer.

40. (New) An electrooptic system for charged-particle beams, the system comprising:

- an upper layer having a plurality of first apertures through which the charged-particle beams pass;
- a middle layer having a plurality of second apertures through which the charged-particle beams pass and a plurality of electrodes;
- a lower layer having a plurality of third apertures through which the charged-particle beams pass;
- a first conductive shield layer interposed between the upper layer and the middle layer; and

a second conductive shield layer interposed between the middle layer and the lower layer.

41. (New) The system according to claim 40, wherein the plurality of electrodes are grouped in units of rows running along a first direction.

42. (New) The system according to claim 40, wherein a first interval between the middle layer and the first conductive shield layer and a second interval between the middle layer and the second conductive shield layer are smaller than a layout pitch of the plurality of electrodes.

43. (New) An electrooptic system for charged-particle beams, the system comprising:
first and second electrooptic systems each including an upper layer, a middle layer, a lower layer, a first conductive shield layer interposed between the upper layer and the middle layer, and a second conductive shield layer interposed between the middle layer and the lower layer, the upper layer having a plurality of first apertures through which the charged-particle beams pass, the middle layer having a plurality of second apertures through which the charged-particle beams pass and a plurality of electrodes, the lower layer having a plurality of third apertures through which the charged-particle beams pass.

44. (New) The system according to claim 43, wherein the plurality of electrodes of the first electrooptic system are grouped in units of rows running along a first direction and the

plurality of electrodes of the second electrooptic system are grouped in units of rows running along a second direction perpendicular to the first direction.

45. (New) The system according to claim 43, wherein the lower layer of the first electrooptic system and the upper layer of the second electrooptic system are formed as one layer.